FROM-PRAXAIR



T-531 P.02/02 F-922

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Assistant Commissioner for Patents Washington, DC 20231

Sir:

GRANT OF ASSOCIATE POWER OF ATTORNEY

I hereby state that I am an attorney of record on this application, having full power of substitution and revocation to prosecute and transact all business in the U.S. Patent and Trademark Office for each application and patent listed on the attached Appendix A.

Wherefore I hereby grant to Blake T. Biederman, Reg. No. 34,124; Donald T. Black, Reg. No. 27,999; Robert J. Follett, Reg. No. 39,566; Stanley Ktorides, Reg. No. 29,399; Bernard Lau, Reg. No. 38,218; David M. Rosenblum. Reg. No. 29,341 and Steven T. Trinker, Reg. No. 28,274, associate power of attorneys to prosecute these applications and to transact all business connected with the applications and issued patents of Appendix A.

Respectfully submitted,

WOOD, HERRON & EVANS, L.L.P.

Donald F. Frei, Esq.

Reg. No. 21,190

August 31, 2000

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Docket No. SubCa Countr Status	021000	021001	021002	021003	021004	021005	021006
Countr	S	S	S	S	SO	SU	<u> </u>
Status	GRANTED	GRANTED	GRANTED	GRANTED	GRANTED	GRANTED	
ApplNum	GRANTED 08/630155	GRANTED 08/608857	GRANTED 08/822055	GRANTED 08/515857	GRANTED 08/856462	GRANTED 08/426246	CBANTED 08/316360
FilDate	10-Apr-199	29-Feb-1996 5879524	24-Mar-1997 5866067	16-Aug-1995 5857611	14-May-1997 5846389	21-Apr-1995 5836506	30 50
Pat No	10-Apr-1996 5896553	6 5879524	7 5866067	5 5857611	7 5846389	5 5836506	30 Soo 1004 5785518
IssDate	20-Apr-1999	09-Mar-1999	02-Feb-1999	12-Jan-1999	08-Dec-1998	17-Nov-1998	
Exposition timel ROOM	10-Apr-2016 SINGLE PHASE TUNGSTEN-TITANIUM SPUTTER TARGETS AND METHOD OF PRODUCING SAME	29-Feb-2016 COMPOSITE BACKING PLATE FOR A SPUTTERING TARGET	27-Mar-2017 HIGH PURITY CHROMIUM METAL BY CASTING WITH CONTROLLED OXYGEN CONTENT	16-Aug-2015 SPUTTER TARGET BACKING PLATE ASSEMBLY AND METHOD OF MAKING SAME	14-May-2017 SPUTTERING TARGET PROTECTION DEVICE	21-Apr-2015 SPUTTER TARGET/BACKING PLATE ASSEMBLY AND METHOD OF MAKING SAME	

021014	021013	021012	021011	021010	021009	021008	021007	Docket No. SubCa Countr Status
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S	S	S	S	S	S	S	S	Countr
GRANTED 08/626320	GRANTED 08/295594	GRANTED 08/577798	GRANTED 08/743472	GRANTED 08/369389	GRANTED 08/667504	GRANTED 08/743305	GRANTED 08/618903	
)8/626320)8/295594)8/577798		08/369389	08/667504	08/743305	08/618903	ApplNum
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641389	656216	5674367	5698158	5700519	5738770	5766380	5783795	Pat No
24-Jun-1997	12-Aug-1997	07-Oct-1997	16-Dec-1997	23-Dec-1997	14-Apr-1998	16-Jun-1998	21-Jul-1998	IssDate
17-Feb-2015 !	12-Aug-2014	22-Dec-2015	04-Nov-2016	06-Jan-2015	21-Jun-2016	05-Nov-2016	20-Mar-2016	ExpDate
17-Feb-2015 MECHANICALLY JOINED SPUTTERING TARGET AND ADAPTER THEREFOR	12-Aug-2014 METHOD FOR MAKING METAL OXIDE SPUTTERING TARGETS(BARRIER POWDER ENVELOPE)	015 SPUTTERING TARGET HAVING A SHRINK FIT MOUNTING RING	04-Nov-2016 VACUUM DISTILLATION APPARATUS FOR PRODUCING ULTRA HIGH PURITY MATERIAL	06-Jan-2015 METHOD FOR PRODUCING ULTRA HIGH PURITY TITANIUM	21-Jun-2016 MECHANICALLY JOINED SPUTTERING TARGET AND ADAPTER THEREFOR	05-Nov-2016 METHOD FOR FABRICATING RANDOMLY ORIENTED ALUMINUM ALLOY SPUTTERING TARGETS WITH FINE GRAINS AND FINE PRECIPITATES	20-Mar-2016 BONDING OF SPUTTERING TARGET BY VARIABLE POLARITY PLASMA ARC WELDING	Title

021022	021021	021020	021019	021018	021017	021016	021015	Docket No. SubCa Countr Status
S	S	S	S	S	S	SO	S	a Countr
GRANTED	GRANTED	GRANTED	GRANTED	GRANTED	GRANTED	GRANTED	GRANTED	Status
GRANTED 08/099185	GRANTED 08/234235	GRANTED 08/161143	GRANTED 08/199627	GRANTED 08/388205	GRANTED 08/390662	GRANTED 08/391047	GRANTED 07/845854	ApplNum
29-Jul-1993 5373994	28-Apr-1994 5431066	02-Dec-1993 5439500	22-Feb-1994 5474667	14-Feb-1995 5490914	17-Feb-1995 5529673	21-Feb-1995 5582630	03-Mar-1992 5632869	FilDate
5373994	5431066	5439500	5474667	5490914	5529673	5582630	5632869	Pat No
20-Dec-1994	11-Jul-1995	08-Aug-1995	12-Dec-1995	13-Feb-1996	25-Jun-1996	10-Dec-1996	27-May-1997	IssDate
20-Dec-2011	28-Apr-2014	08-Aug-2012	22-Feb-2014	14-Feb-2015	17-Feb-2015	21-Feb-2015	27-May-2014	ExpDate
20-Dec-2011 BALL MILL CAN POSITIONING DEVICE	28-Apr-2014 DEVICE FOR PREPARING SAMPLES OF POWDERED METALS FOR ANALYSIS	08-Aug-2012 MAGNETO-OPTICAL ALLOY SPUTTER TARGETS	REDUCED STRESS SPUTTERING TARGET AND MEHTOD OF MANUFACTURING THEREFOR	14-Feb-2015 HIGH UTLIZATION SPUTTERING TARGET FOR CATHODE ASSEMBLY	17-Feb-2015 MECHANICALLY JOINED SPUTTERING TARGET AND ADAPTER THEREFOR	21-Feb-2015 ULTRA HIGH PURITY MAGNESIUM VACUUM DISTILLATION PURIFICATION METHOD	27-May-2014 METHOD OF PRETEXTURING A CATHODE SPUTTERING COATING AN ARTICLE THEREWITH	Title

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021030	021029	021028	021027	021026	021025	021024	021023	Docket No. SubCa
S	S	S	S	S	S	S	S	1
GRANTED 08/911539	GRANTED 08/910334	PENDING	GRANTED 08/885943	PENDING	PENDING 08/295593	GRANTED 07/910644	GRANTED 07/967458	Countr Status
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14-Aug-1997 6045634	13-Aug-1997 6056857	24-Jul-1997	30-Jun-1997 5989673	25-Jun-1997	25-Aug-1994	08-Jul-1992 5230462	28-Oct-1992 5336386	FilDate
6045634	6056857		5989673			5230462	5336386	Pat No
04-Apr-2000	02-May-2000		23-Nov-1999			27-Jul-1993	09-Aug-1994	IssDate
14-Aug-2017	13-Aug-2017	24-Jul-2017	30-Jun-2017	25-Jun-2017	25-Aug-2014	27-Jul-2010	09-Aug-2011	ExpDate
14-Aug-2017 HIGH PURITY TITANIUM SPUTTERING TARGET AND METHOD OF MAKING	13-Aug-2017 CRYOGENIC ANNEALING OF SPUTTERING TARGET	24-Jul-2017 METHODS FOR PRODUCING ULTRA HIGH PURITY TITANIUM	30-Jun-2017 CHROMIUM-TANTALUM OXIDES (Ca-TaOx), SPUTTERING TARGETS AND THIN FILM SEEDLAYER/SUBLAYERS FOR THIN FILM MAGNETIC RECORDING MEDIA	25-Jun-2017 MECHANICALLY JOINED SPUTTERING TARGET AND ADAPTOR THEREFOR	25-Aug-2014 APPARATUS AND METHOD FOR MAKING METAL OXIDE SPUTTERING TARGETS	27-Jul-2010 METHOD OF SOLDERING A SPUTTERING TARGET TO A BACKING MEMBER	09-Aug-2011 TARGET FOR CATHODE SPUTTERING	Title

021037	021036	021035	021034	021033	021032	021031	021030-1	Docket No. SubCa Countr Status
S	S	S	S	S	S	S	S	a Countr
PENDING 09/151923	GRANTED 09/088454	GRANTED 09/057932	GRANTED 09/047849	GRANTED 09/054146	GRANTED 09/024552	GRANTED 08/926375	PENDING	Status
09/151923	09/088454	09/057932	09/047849	09/054146	09/024552	08/926375	09/501220	ApplNum
11-Sep-1998	01-Jun-1998 6086735	09-Apr-1998 6039788	25-Mar-1998 5993734	02-Apr-1998 5993575	17-Feb-1998 6091046	09-Sep-1997 6010583	10-Feb-2000	FilDate
	6086735	6039788	5993734	5993575	6091046	6010583		Pat No
	11-Jul-2000	21-Mar-2000	30-Nov-1999	30-Nov-1999	18-Jul-2000	04-Jan-2000		IssDate
11-Sep-2018 /	01-Jun-2018 (24-Mar-2017	25-Mar-2018	05-Nov-2016	20-Mar-2016	09-Sep-2017	17	ExpDate
AUTOMATION OF HEAT TREATMENT FURNACES	CONTOURED SPUTTERING TARGET	17 MELTING AND CASTING OF HIGH PURITY CHROMIUM WITH CONTROLLED OXYGEN CONTENT	METHOD FOR MAKING W/Ti SPUTTERING TARGETS AND PRODUCT IN AN INERT ATMOSPHERE	METHOD FOR FABRICATING RANDOMLY ORIENTED ALUMINUM ALLOY SPUTTERING TARGETS WITH FINE GRAINS AND IFNE PRECIPITATES	BONDING OF SPUTTERING TARGET BY VARIABLE POLARITY PLASMA ARC WELDING	METHOD OF MAKING AN UNREACTED METAL-ALUMINUM SPUTTERING TARGET	HIGH PURITY TITANIUM SPUTTERING TARGET AND METHOD OF MAKING	Tide

021044	021043	021042	021041	021040	021039-1	021039	Docket No. SubCa 021038
S	S	S	S	S	S	S	
GRANTED	PENDING	PENDING	PENDING	PENDING	PENDING	GRANTED	Countr Status US Pending
GRANTED 08/850707	09/283084	09/260300	09/226792	09/220906	09/511440	GRANTED 09/172311	<i>ApplNum</i> 09/146600
02-May-1997 6030514	31-Mar-1999	02-Mar-1999	07-Jan-1999	24-Dec-1998	23-Feb-2000	14-Oct-1998 6073830	FilDate Pat No
29-Feb-2000						13-Jun-2000	IssDate
02-May-2017	31-Mar-2019	02-Mar-2019	16-Aug-2015	24-Dec-2018	14-Oct-2018	14-Oct-2018	ExpDate 03-Sep-2018
02-May-2017 METHOD OF REDUCING SPUTTERING BURN- IN TIME, MINIMIZING SPUTTERED PARTICULATE, AND TARGET ASSEMBLY THEREFOR	31-Mar-2019 NICKEL/VANADIUM SPUTTERING TARGET WITH ULTRA-LOW ALPHA EMISSION	02-Mar-2019 REFRACTORY COATED INDUCTION COIL FOR USE IN THIN FILM DEPOSITION AND METHOD FOR MAKING SAME	16-Aug-2015 SPUTTER TARGET/BACKING PLATE ASSEMBLY AND METHOD OF MAKING SAME	24-Dec-2018 METHOD OF MAKING HIGH DENSITY, HIGH PURITY TUNGSTEN TARGET	14-Oct-2018 SPUTTER TARGET/BACKING PLATE ASSEMBLY AND METHOD OF MAKING SAME	14-Oct-2018 SPUTTER TARGET/BACKING PLATE ASSEMBLY AND METHOD OF MAKING SAME	ExpDate Title 03-Sep-2018 METHOD OF MANUFACTURING ENHANCED FINISH SPUTTERING TARGETS

021052	021051	021050	021049	021048	021047	021046	021045	Docket No. SubCa Countr Status
US	S	S	S	S	S	S	S	ubCa Cou
GRANTED	PENDING	PENDING	PENDING	PENDING	PENDING	PENDING	WITHDRA	ıtr Status
GRANTED 09/366453	PENDING 09/353503	PENDING 09/349666	PENDING 09/349687	09/368062	09/349285	PENDING 09/377587	WITHDRA 09/260295	ApplNum
03-Aug-1999 6042777	14-Jul-1999	08-Jul-1999	08-Jul-1999	03-Aug-1999	08-Jul-1999	19-Aug-1999	02-Mar-1999	FilDate
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28-Mar-2000								IssDate
03-Aug-2019	14-Jul-2019	08-Jul-2019	08-Jul-2019	03-Aug-2019	08-Jul-2019	19-Aug-2019	02-Mar-2019	ExpDate
03-Aug-2019 MANUFACTURING OF HIGH DENSITY INTERMETALLIC SPUTTER TARGETS	14-Jul-2019 HIGH PERFORMANCE Cu/Cr TARGETS FOR SEMICONDUCTOR APPLICATIONS	08-Jul-2019 METHOD OF MAKING HIGH DENSITY SPUTTERING TARGETS	2019 FABRICATION AND BONDING OF COPPER AND COPPER ALLOY SPUTTERING TARGETS	03-Aug-2019 FABRICATION OF CLAD HOLLOW CATHODE MAGNETRON TARGETS	08-Jul-2019 METHOD OF BONDING SPUTTERING TARGETS TO BACKING PLATES	19-Aug-2019 LOW PERMEABILITY NON-PLANAR FERROMAGNETIC SPUTTER TARGETS	02-Mar-2019 METHOD OF MANUFACTURING AND REFILLING OF SPUTTER TARGETS BY THERMAL SPRAY FOR USE AND REUSE AND REUSE IN THIN FILM DEPOSITION	Title

021057	021056	021055	021054	021053	Docket No. SubCa Countr Status ApplNum
SU	S	S	S	S	Countr
PENDING	PENDING	PENDING	PENDING	GRANTED	Status
PENDING 09/430988	PENDING 09/431745	PENDING 09/413073	PENDING 09/401936	GRANTED 09/396276	ApplNum
01-Nov-1999	01-Nov-1999	06-Oct-1999	23-Sep-1999	15-Sep-1999 6092427	FilDate Pat No
				25-Jul-2000	IssDate
01-Nov-2019 METHOD OF MAKING LOW MAGNETIC PERMEABILITY COBALT SPUTTER TARGETS	01-Nov-2019 DETERMINATION OF ACTUAL DEFECT SIZE IN CATHODE SPUTTER TARGETS SUBJECTED TO ULTRASONIC INSPECTION	06-Oct-2019 HIGH MAGNETIC FLUX SPUTTERING TARGETS WITH VARIOUS MAGNETIC PERMEABILITY IN SELECTED REGIONS	23-Sep-2019 EXTENDED LIFE SPUTTER TARGETS	15-Sep-2019 METHOD OF PREPARING BOND INTERFACE EVALUATION COUPON	ExpDate Title